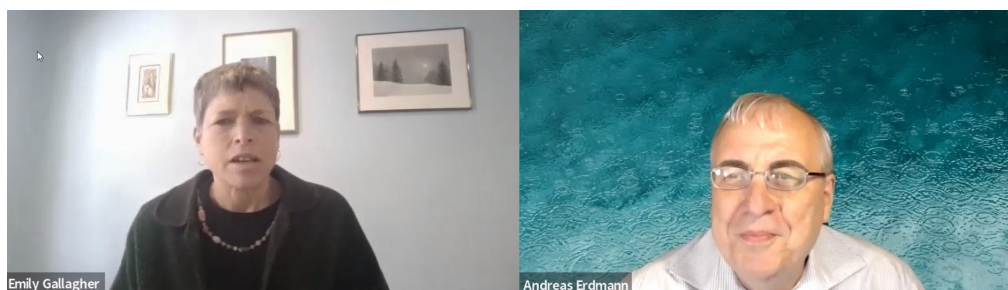


Attenuated phase shift masks: an interview with Andreas Erdmann

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Abstract. JM3 Associate Editor Emily Gallagher, a principal researcher at imec, interviews Andreas Erdmann, head of the Fraunhofer IISB Computational Lithography and Optics Group. With Hazem Mesilhy and Peter Evanschitzky, Erdmann is the lead author of “[Attenuated phase shift masks: a wild card resolution enhancement for extreme ultraviolet lithography?](#),” a review paper in the April-June 2022 issue of the *Journal of Micro/Nanopatterning, Materials, and Metrology*. [DOI: [10.1117/1.JMM.21.4.040402](https://doi.org/10.1117/1.JMM.21.4.040402)]



JM3 Associate Editor Emily Gallagher, a principal researcher at imec, interviews Andreas Erdmann. View the interview at <https://doi.org/10.1117/1.JMM.21.4.040402.s1>.

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